

Title (en)

METHOD FOR DEPOSITING CHALCOGENIDE THIN FILMS

Title (de)

VERFAHREN ZUR ABSCHEIDUNG VON CHALKOGENID-DÜNNSCHICHTEN

Title (fr)

PROCEDE DE DÉPÔT DE FILMS MINCES DE CHALCOGENURE

Publication

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Application

EP 17804615 A 20171031

Priority

- FR 1660583 A 20161102
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Abstract (en)

[origin: WO2018083415A1] The invention relates to a device for depositing at least one radical chalcogenide thin film on an element to be treated including an intake area (4) and a diffusion area (6) receiving the element (P) to be treated, the intake area (4) and the diffusion area (6) extending along a longitudinal axis (Z), a radical hydrogen source (8) connected to the intake area (4), pumping means (19), means for injecting a reagent reacting with the radical hydrogen to form H₂S, and means for supplying a precursor to the diffusion area. The injection means inject the reagent into a central area of the intake area (4) in the longitudinal direction within the radical hydrogen flow. The pumping means (19) are controlled so as to operate during the reagent injection, and generate a flow of H₂S along the element to be treated (P) in order to activate said element so as to absorb the precursor.

IPC 8 full level

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CPC (source: EP US)

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Citation (search report)

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Designated extension state (EPC)

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DOCDB simple family (publication)

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